

## **"New SIPP Technology"**

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Abstract: New developments in HPPMS / HiPIMS PULSE Technology with very high peak pulsed DC plasma power supplies using combined DC or Medium Frequency (MF) offer significant advantages in the plasma and surface technologies. This technology is applicable for single and dual magnetron applications and synchronized pulsed bias. This allows higher process rates for metallic and reactive sputtering applications. Processes such as Co-Sputtering with different target materials using Dual Magnetron Systems and asymmetric bipolar pulse modes are possible. Applicable HPPMS / HiPIMS Pulse packages with superimposed DC or MF sputtering open a new field of applications.